

**Notice of References Cited**

Application/Control No.

10/530,848

Applicant(s)/Patent Under  
Reexamination  
ABERLE ET AL.

Examiner

JULIA SLUTSKER

Art Unit

2891

Page 1 of 1

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-2002/0052096 A1	05-2002	Zhang et al.	438/487
*	B	US-6,620,743 B2	09-2003	Pagliaro et al.	438/787
	C	US-			
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	K	US-			
	L	US-			
	M	US-			

**FOREIGN PATENT DOCUMENTS**

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**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Aberle et al. "Formation of large-grained uniform poly-Si films on glass at low temperature", Journ Crystl.Growth, 226, (2001), pp.209-214
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	W	
	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.